

SUBSTITUTE SPECIFICATION

METHOD FOR FORMING THICK FILM PATTERN, METHOD FOR MANUFACTURING
ELECTRONIC COMPONENT, AND PHOTOLITHOGRAPHY PHOTSENSITIVE PASTE

5

BACKGROUND OF THE INVENTION

1. Field of the Invention

The present invention relates to a method for forming a
thick film pattern by using photolithography, a method for
10 manufacturing an electronic component, and a photolithography
photosensitive paste to be used for forming a thick film pattern
via photolithography.

2. Description of the Related Art

15 As densities have been increased and signal speeds have been
increased for high-frequency electronic apparatuses, patterns,
e.g., wiring conductors, constituting high-frequency circuits
provided in these apparatuses have been required to be fine, have
large film thicknesses, have rectangular cross-sectional shapes,
20 and furthermore, have wiring precision with very narrow ranges of
variations in wiring dimensions.

A method for forming a pattern via photolithography has been
widely used as a method for forming such a fine pattern. For
example, a photosensitive paste containing an inorganic powder, a
25 photosensitive monomer, a polymer, a photopolymerization
initiator, and the like has been proposed and known as the

photosensitive paste to be used therein (for example, Japanese Unexamined Patent Application Publication No. 2002-82449).

However, in the case where patterns are formed via photolithography, known photosensitive pastes have a problem in that an adequate photo-curing depth (a depth from a thick film surface, at which the energy of radiated light, e.g., ultraviolet light, travelling in the thick film falls below the minimum energy required for curing a resin due to attenuation by being consumed for curing the resin or being absorbed by the resin component) cannot be ensured.

The inventors of the present invention found that the polymer exerted an influence on this photo-curing depth. The reasons for this are believed to be that (a) the radiated light is refracted and scattered by the polymer and, therefore, it becomes difficult for the ultraviolet light to reach the inside of the photosensitive paste, (b) the ultraviolet light is absorbed by the polymer, and (c) when the polymer is contained, the micro-Brownian motion of the monomer in the photosensitive paste is hindered and, thereby, the polymerization becomes hard to proceed.

SUMMARY OF THE INVENTION

In order to overcome the above-described problems, preferred embodiments of the present invention provide a method for forming a thick film pattern, the method being capable of efficiently forming via photolithography a thick film pattern having a large

thickness and exhibiting high dimension precision and high shape precision, a method for manufacturing an electronic component by using the thick film pattern, and a photolithography photosensitive paste suitable for being used therefor.

5 A method for forming a thick film pattern according to a preferred embodiment of the present invention includes the steps of applying to a support a photosensitive paste including an inorganic powder, a photosensitive monomer, and a photopolymerization initiator and containing substantially no
10 polymer so as to form a photosensitive paste film, subjecting the photosensitive paste film to an exposure treatment, and developing the photosensitive paste film subjected to the exposure treatment so as to form a predetermined thick film pattern.

15 A method for forming a thick film pattern according to another preferred embodiment of the present invention includes the steps of applying to a support a photosensitive paste including an inorganic powder, a photosensitive monomer, a photopolymerization initiator, and a polymer, wherein a ratio
20 (weight ratio) of the photosensitive monomer to a total amount of the photosensitive monomer and the polymer satisfies the condition represented by the following Formula (1):

$$\text{photosensitive monomer}/(\text{photosensitive monomer} + \text{polymer}) \geq 0.86 \quad (1)$$

25 so as to form a photosensitive paste film, subjecting the photosensitive paste film to an exposure treatment, and

developing the photosensitive paste film subjected to the above-described exposure treatment so as to form a predetermined thick film pattern.

A method for forming a thick film pattern according to another preferred embodiment of the present invention is characterized in that the contents of the inorganic powder, the photosensitive monomer, and the photopolymerization initiator constituting the photosensitive paste are within the following ranges:

inorganic powder: about 60 to about 90 percent by weight,
photosensitive monomer: about 5 to about 39 percent by weight, and

photopolymerization initiator: about 1 to about 10 percent by weight.

A method for forming a thick film pattern according to another preferred embodiment of the present invention is characterized in that a photosensitive paste containing a photosensitive monomer having a double bond concentration within the range of about 8 mmol/g to about 11 mmol/g is preferably used as the photosensitive paste.

A method for forming a thick film pattern according to a further preferred embodiment of the present invention is characterized in that a photosensitive paste including a photosensitive monomer having an ethylene oxide structure with a degree of polymerization of about 3 or less is preferably used as the photosensitive paste.

A method for forming a thick film pattern according to a further preferred embodiment of the present invention is characterized in that the photosensitive paste includes an ultraviolet absorber.

5 A method for forming a thick film pattern according to another preferred embodiment of the present invention is characterized in that the photosensitive paste includes a solvent in a proportion of about 5 percent by weight or less.

10 A method for forming a thick film pattern according to a further preferred embodiment of the present invention is characterized in that development is conducted by using an organic solvent in the development step.

15 A method for forming a thick film pattern according to a further preferred embodiment of the present invention is characterized in that the exposure treatment is conducted while the photosensitive paste film and a photomask are arranged so as to be kept from contacting with each other in the exposure step.

20 A method for forming a thick film pattern according to a further preferred embodiment of the present invention is characterized in that the photosensitive paste is subjected to the exposure treatment without using a photomask in the exposure step.

25 A method for manufacturing an electronic component according to a preferred embodiment of the present invention includes the steps of forming a thick film pattern by the method according to any one of the above-described preferred embodiments, and then

firing the thick film pattern.

A photolithography photosensitive paste according to a preferred embodiment of the present invention is characterized by including an inorganic powder, a photosensitive monomer, and a photopolymerization initiator and containing substantially no polymer.

A photolithography photosensitive paste according to a preferred embodiment of the present invention includes an inorganic powder, a photosensitive monomer, a photopolymerization initiator, and a polymer, wherein a ratio (weight ratio) of the photosensitive monomer to a total amount of the photosensitive monomer and the polymer satisfies the condition represented by the following Formula (1):

$$\frac{\text{photosensitive monomer}}{\text{photosensitive monomer} + \text{polymer}} \geq 0.86 \quad (1).$$

A photolithography photosensitive paste according to a further preferred embodiment of the present invention is characterized in that the contents of the inorganic powder, the photosensitive monomer, and the photopolymerization initiator are within the following ranges:

inorganic powder: about 60 to about 90 percent by weight,
photosensitive monomer: about 5 to about 39 percent by weight, and

photopolymerization initiator: about 1 to about 10 percent by weight.

A photolithography photosensitive paste according to a

further preferred embodiment of the present invention is characterized in that the photosensitive monomer is a photosensitive monomer having a double bond concentration within the range of about 8 mmol/g to about 11 mmol/g.

5 A photolithography photosensitive paste according to a further preferred embodiment of the present invention is characterized in that the photosensitive monomer is a photosensitive monomer having an ethylene oxide structure with a degree of polymerization of about 3 or less.

10 A photolithography photosensitive paste according to a further preferred embodiment of the present invention is characterized by including an ultraviolet absorber.

 A photolithography photosensitive paste according to a further preferred embodiment of the present invention is
15 characterized by including a solvent in a proportion of about 5 percent by weight or less.

 In the method for forming a thick film pattern according to a preferred embodiment of the present invention, the photosensitive paste including the inorganic powder, the
20 photosensitive monomer, and the photopolymerization initiator and containing substantially no polymer is applied to the support so as to form the photosensitive paste film, the resulting photosensitive paste film is subjected to the exposure treatment, and thereafter, the development is conducted so as to form a
25 predetermined thick film pattern. Therefore, it becomes possible to efficiently form a thick film pattern having a large thickness

and exhibiting high dimension precision and high shape precision.

That is, since the photosensitive paste containing substantially no polymer is used, in the exposure step, refraction, scattering, absorption, and the like of the radiated light by the polymer do not occur, the ultraviolet light easily reaches the inside of the photosensitive paste film, the micro-Brownian motion of the photosensitive monomer is not hindered by the polymer, and the polymerization is prevented from becoming hard to proceed. Consequently, it becomes possible to form a thick film pattern having a large thickness, a high hardness, and a high aspect ratio and exhibiting high dimension precision and high shape precision.

In various preferred embodiments of the present invention, that a photosensitive paste "contains substantially no polymer" means that the present invention includes the case where a very small amount of polymer is contained as an impurity in a photosensitive paste.

In the case where the photosensitive paste containing the polymer is used as in the method for forming a thick film pattern according to a preferred embodiment of the present invention as well, when a ratio (weight ratio) of the photosensitive monomer to a total amount of the photosensitive monomer and the polymer satisfies the condition represented by $\text{photosensitive monomer} / (\text{photosensitive monomer} + \text{polymer}) \geq 0.86$, that is, when the ratio of the polymer to the total amount of the photosensitive monomer and the polymer is less than about 0.14 on

a weight ratio basis (less than about 14 percent by weight), in the exposure step, refraction, scattering, absorption, and the like of the radiated light by the polymer can be reduced, the ultraviolet light easily reaches the inside of the photosensitive paste film, and the micro-Brownian motion of the photosensitive monomer is prevented from being hindered by the polymer.

Consequently, it becomes possible to form reliably a thick film pattern having a large thickness and exhibiting high dimension precision and high shape precision.

When the contents of the inorganic powder, the photosensitive monomer, and the photopolymerization initiator constituting the photosensitive paste are specified to be within the following ranges:

inorganic powder: about 60 to about 90 percent by weight,

photosensitive monomer: about 5 to about 39 percent by weight, and

photopolymerization initiator: about 1 to about 10 percent by weight

the value of photo-curing depth of the photosensitive paste can be increased. Consequently, it becomes possible to efficiently form a thick film pattern having a large thickness and exhibiting high dimension precision and high shape precision by using the photosensitive paste.

When the photosensitive paste containing a photosensitive monomer having a double bond concentration within the range of about 8 mmol/g to about 11 mmol/g is used as the photosensitive

paste, it becomes possible to increase the photo-curing depth and, therefore, the present invention is allowed to become more effective.

When the photosensitive paste containing a photosensitive
5 monomer having an ethylene oxide structure with a degree of polymerization of about 3 or less is used as the photosensitive paste, it becomes possible to increase the value of photo-curing depth. This is preferable.

When the photosensitive paste including an ultraviolet
10 absorber is used, it becomes possible to achieve a deeper photo-curing depth by a small amount of exposure and, therefore, a thick film pattern having a large thickness and exhibiting high dimension precision and high shape precision can be formed efficiently.

15 When the photosensitive paste including a solvent in a proportion of about 5 percent by weight or less is used, a drying step is allowed to become unnecessary or the drying step is allowed to be simplified and, therefore, the present invention is allowed to become more effective.

20 When the development is conducted by using the organic solvent in the development step, impurities do not enter the pattern, and a rinse step is allowed to become unnecessary or the rinse step is allowed to be simplified. Therefore, the development can easily and speedily be conducted and the present
25 invention is allowed to become more effective.

When the exposure treatment is conducted while the

photosensitive paste film and the photomask are disposed in such a way as to be kept from contacting with each other in the exposure step, the photosensitive paste film is prevented from being damaged due to contact with the photomask. Therefore, it
5 becomes possible to form a highly reliable thick film pattern.

When the photosensitive paste is subjected to the exposure treatment without using a photomask in the exposure step, the photomask becomes unnecessary. Consequently, the cost can be reduced, the manufacturing step is allowed to be simplified and,
10 therefore, the present invention is allowed to become more effective.

In the method for manufacturing an electronic component according to one of the preferred embodiments of the present invention, after the thick film pattern is formed by the method
15 according to any one of the other preferred embodiments of the present invention, the resulting thick film pattern is fired. Consequently, it becomes possible to produce efficiently and reliably a high-performance, highly reliable electronic component provided with a fine pattern.

20 The photolithography photosensitive paste according to a preferred embodiment of the present invention includes the inorganic powder, the photosensitive monomer, and the photopolymerization initiator and contains substantially no polymer. Consequently, in the exposure step, since refraction,
25 scattering, absorption, and the like of the radiated light by the polymer do not occur, the ultraviolet light easily reaches the

inside of the photosensitive paste film, the micro-Brownian motion of the photosensitive monomer is not hindered by the polymer, and the polymerization tends to proceed. Therefore, it becomes possible to reliably form a thick film pattern exhibiting high dimension precision and high shape precision by using the photolithography photosensitive paste according to the present invention.

In the case where the polymer is included, when the ratio (weight ratio) of the photosensitive monomer to a total amount of the photosensitive monomer and the polymer satisfies the condition represented by $\text{photosensitive monomer} / (\text{photosensitive monomer} + \text{polymer}) \geq 0.86$, that is, when the ratio of the polymer to the total amount of the photosensitive monomer and the polymer is less than about 0.14 on a weight ratio basis (less than about 14 percent by weight), in the exposure step, refraction, scattering, absorption, and the like of the radiated light by the polymer can be reduced, the ultraviolet light easily reaches the inside of the photolithography photosensitive paste film, and the micro-Brownian motion of the photosensitive monomer is prevented from being hindered by the polymer. Consequently, it becomes possible to reliably form a thick film pattern having a large thickness and exhibiting high dimension precision and high shape precision.

When the contents of the inorganic powder, the photosensitive monomer, and the photopolymerization initiator constituting the photolithography photosensitive paste are within

the following ranges:

inorganic powder: about 60 to about 90 percent by weight,

photosensitive monomer: about 5 to about 39 percent by weight, and

5 photopolymerization initiator: about 1 to about 10 percent by weight,

a photolithography photosensitive paste having a large value of photo-curing depth can be produced. Consequently, it becomes possible to form efficiently a thick film pattern having a large
10 thickness and exhibiting high dimension precision and high shape precision by using the photolithography photosensitive paste.

When the photolithography photosensitive paste contains the photosensitive monomer having a double bond concentration within the range of about 8 mmol/g to about 11 mmol/g as the
15 photosensitive monomer, it becomes possible to increase the photo-curing depth and, therefore, the present invention is allowed to become more effective.

When the photolithography photosensitive paste includes the photosensitive monomer having an ethylene oxide structure with a
20 degree of polymerization of about 3 or less as the photosensitive paste, it becomes possible to increase the value of photo-curing depth particularly and, therefore, the present invention is allowed to become more effective.

When the photolithography photosensitive paste includes an
25 ultraviolet absorber, it becomes possible to achieve a deeper photo-curing depth by a small amount of exposure and, therefore,

a thick film pattern having a large thickness and exhibiting high dimension precision and high shape precision can be formed efficiently. Consequently, the present invention is allowed to become more effective.

5 When the photolithography photosensitive paste contains a solvent in a proportion of about 5 percent by weight or less, it becomes possible to form a thick film pattern without conducting drying or with drying for a minimum drying time. Therefore, the present invention is allowed to become more effective.

10 Other features, elements, steps, characteristics and advantages of the present invention will become more apparent from the following detailed description of preferred embodiments thereof with reference to the attached drawings.

BRIEF DESCRIPTION OF THE DRAWINGS

Figs. 1(a) to (c) are diagrams showing a method for forming a thick film pattern by a method according to a preferred embodiment of the present invention.

5 Figs. 2(a) to (d) are diagrams showing a method for forming a thick film pattern by another method according to a further preferred embodiment of the present invention.

Fig. 3 is a sectional view showing an electronic component (ceramic multilayer substrate) according to another preferred
10 embodiment of the present invention.

Fig. 4 is a perspective view showing an appearance of a chip coil according to another preferred embodiment of the present invention.

Fig. 5 is a perspective exploded view showing a
15 configuration of the chip coil shown in Fig. 4.

DETAILED DESCRIPTION OF PREFERRED EMBODIMENTS

When a method for forming a thick film pattern according to a preferred embodiment of the present invention is carried out,
20 it is desirable that a photosensitive paste usually having inorganic powder, photosensitive monomer, and photopolymerization initiator have contents within the following ranges:

(a) inorganic powder: about 60 to about 90 percent by weight

(b) photosensitive monomer: about 5 to about 39 percent by
25 weight

(c) photopolymerization initiator: about 1 to about 10

percent by weight, respectively.

The content of the inorganic powder is specified to be within the range of about 60 to about 90 percent by weight and, thereby, in the case where a metal powder is used as the inorganic powder, it becomes possible to prevent an occurrence of poor electrical conductivity (increase in conductor resistance). In the case where a ceramic material powder or a glass powder is used as the inorganic powder, it becomes possible to prevent an occurrence of poor insulation.

Furthermore, when the content of the inorganic powder is specified to be within the range of about 60 to about 90 percent by weight, an excessive increase in viscosity of the photosensitive paste, difficulty of handling, deterioration of printability, and the like do not occur, and it becomes possible to keep good photo-curability. In addition, reduction in strength of a cured material and embrittlement of a cured material can be prevented.

With respect to the range of particle diameter of the inorganic powder, when the average particle diameter is specified to be within the range of about 0.1 μm to about 10 μm , agglomeration of particles is suppressed, good dispersibility is maintained, and it becomes possible to produce a fine pattern. In addition, it becomes possible to produce a photosensitive paste having adequate photo-curability and, therefore, this is preferable. It is more preferable that an inorganic powder having an average particle diameter of about 0.5 μm to about 5 μm

is used.

Preferably, a spherical inorganic powder is used. However, an inorganic powder in the shape of foil, a granule, a block, a flat material, a plate, a rod, a needle, and the like can also be used, and the shape can be selected appropriately depending on a thick film pattern to be formed.

Alternatively, an electrically conductive powder, a ceramic powder, a glass powder, and the like can be used as the inorganic powder.

Examples of usable electrically conductive powder include Ag, Au, Pt, Pd, Cu, Ni, W, Al, and Mo, and these can also be used in combination. An alloy containing at least one type of the above-described metals can also be used. Furthermore, a metal powder provided with an oxide coating, a nitride coating, or a silicide coating can also be used.

Examples of usable ceramic powders include an oxide, a boride, a nitride, a silicide, and the like of at least one type of metal selected from the group consisting of Al, Ag, Cu, Ni, Ti, Ba, Pb, Zr, Mn, Cr, Sr, Fe, Y, Nb, La, Si, Zn, Bi, B and Ru. A glass composite based ceramic powder can also be used.

Known glass powders, e.g., a borosilicate based glass powder, can be used as the glass powder. More specifically, examples of usable glass powders include glass powders of SiO_2 -PbO base, SiO_2 -ZnO base, SiO_2 - Bi_2O_3 base, SiO_2 - K_2O base, SiO_2 - Na_2O base, PbO - B_2O_3 base, SiO_2 -ZnO- B_2O_3 base, SiO_2 - Bi_2O_3 - B_2O_3 base, SiO_2 - K_2O - B_2O_3 base, and SiO_2 - Na_2O - B_2O_3 base.

It is possible that the above-described substances are used as the inorganic powder by mixing, that is, Ag and glass can be used by mixing, for example.

It is desirable that the ratio of the photosensitive monomer is within the range of about 5 to about 39 percent by weight, as described above. This is because it becomes possible to prevent reduction in photo-curability and the resulting reduction in strength of a cured material (embrittlement of a cured material) by specifying the proportion of the photosensitive monomer to be within the range of about 5 to about 39 percent by weight and, in addition, it becomes possible to avoid excessive reduction in the proportion of the inorganic powder, while these are preferable.

Examples of photosensitive monomers include stearyl acrylate, tetrahydrofurfuryl acrylate, lauryl acrylate, 2-phenoxyethyl acrylate, isodecyl acrylate, isooctyl acrylate, tridecyl acrylate, caprolactone acrylate, ethoxylated nonylphenol acrylate, 1,4-butanediol diacrylate, diethylene glycol diacrylate, tetraethylene glycol diacrylate, triethylene glycol diacrylate, ethoxylated bisphenol A diacrylate, propoxylated neopentyl glycol diacrylate, tris(2-hydroxyethyl)isocyanurate triacrylate, propoxylated trimethylolpropane triacrylate, propoxylated glyceryl triacrylate, pentaerythritol tetraacrylate, tetrahydrofurfuryl methacrylate, cyclohexyl methacrylate, isodecyl methacrylate, lauryl methacrylate, triethylene glycol dimethacrylate, tetraethylene glycol dimethacrylate, 1,9-nonanediol diacrylate, 1,6-hexanediol dimethacrylate, neopentyl

glycol dimethacrylate, ethoxylated bisphenol A dimethacrylate, ethoxylated isocyanuric acid diacrylate, ethoxylated paracumylphenol acrylate, ethylhexylcarbitol acrylate, N-vinyl-2-pyrrolidone, isobornyl acrylate, and polypropylene glycol diacrylate.

When a monomer having a double bond concentration within the range of about 8 mmol/g to about 11 mmol/g is used as the photosensitive monomer, in particular, it becomes possible to improve the photo-curing depth.

Examples of photosensitive monomers having a double bond concentration within the range of about 8 mmol/g to about 11 mmol/g include hexanediol triacrylate, tripropylene glycol triacrylate, trimethylolpropane triacrylate, 1,3-butanediol diacrylate, pentaerythritol triacrylate, ditrimethylolpropane tetraacrylate, dipentaerythritolhydroxy pentaacrylate, ethoxylated pentaerythritol tetraacrylate, ethylene glycol dimethacrylate, 1,4-butanediol dimethacrylate, diethylene glycol dimethacrylate, 1,3-butylene glycol dimethacrylate, trimethylolpropane triacrylate, dipentaerythritol pentaacrylate, and dipentaerythritol hexaacrylate.

When a photosensitive paste containing a photosensitive monomer having an ethylene oxide structure with a degree of polymerization of about 3 or less is used, it becomes possible to improve the photo-curing depth. That is, in the case where the degree of polymerization of the ethylene oxide structure is about 3 or less and, therefore, is low, the effect of improving the

photo-curing depth is enhanced.

Examples of photosensitive monomers having an ethylene oxide structure with a degree of polymerization of about 3 or less include ethoxylated (ethylene oxide-modified) compounds, e.g.,
5 ethoxylated trimethylolpropane triacrylate, and polyethylene glycol diacrylate.

It is desirable that the photopolymerization initiator within the range of about 1 to about 10 percent by weight is included. When the photopolymerization initiator is specified to
10 be within the range of about 1 to about 10 percent by weight, poor photo-curability and reduction in hardness of the cured material due to shortage of photopolymerization initiator are avoided, and it becomes possible to form a pattern having a high aspect ratio. In addition, it becomes possible to prevent the
15 energy from not reaching the inside due to excessive absorption of the ultraviolet light by the photosensitive paste. Consequently, it becomes possible to reliably form a pattern having an adequate thickness and exhibiting high hardness of cured material and, therefore, this is preferable.

20 Examples of photopolymerization initiators suitable for use in the present invention include benzil, benzoin ethyl ether, benzoin isobutyl ether, benzoin isopropyl ether, benzophenone, benzoylbenzoic acid, methyl benzoyl benzoate, 4-benzoyl-4'-methyldiphenyl sulfide, benzyl dimethyl ketal, 2-n-butoxy-4-
25 dimethylaminobenzoate, 2-chlorothioxanthone, 2,4-diethylthioxanthone, 2,4-diisopropylthioxanthone,

isopropylthioxanthone, 2-dimethylaminoethyl benzoate, ethyl p-dimethylaminobenzoate, isoamyl p-dimethylaminobenzoate, 3,3'-dimethyl-4-methoxybenzophenone, 2,4-dimethylthioxanthone, 1-(4-dodecylphenyl)-2-hydroxy-2-methylpropane-1-on, 2,2-dimethoxy-1,2-diphenylethane-1-on, hydroxycyclohexyl phenyl ketone, 2-hydroxy-2-methyl-1-phenylpropane-1-on, 1-[4-(2-hydroxyethoxy)-phenyl]-2-methyl-1-propane-1-on, 2-methyl-1-[4-(methylthio)phenyl]-2-morpholinopropane-1-on, methylbenzoylformate, 1-phenyl-1,2-propanedion-2-(o-ethoxycarbonyl)oxime, 2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-1-butanone, bis(2,6-dimethoxybenzoyl)-2,4,4-trimethylpentylphosphine oxide, bis(2,4,6-trimethylbenzoyl)phenylphosphine oxide, bis(2,4,6-trimethylbenzoyl)-2,4,4-trimethylpentylphosphine oxide, bis(2,6-dichlorobenzoyl)-2,4,4-trimethylpentylphosphine oxide, 1-(4-isopropylphenyl)-2-hydroxy-2-methylpropane-1-on, 1,2-diphenylethanedion, and methylphenyl glyoxylate. These photopolymerization initiators may be used alone or at least two types thereof may be used at the same time.

In some cases, photosensitizers may be added. Examples of photosensitizers include p-dimethylaminobenzoic acid isoamyl ester and p-dimethylaminobenzoic acid ethyl ester.

A photosensitive paste containing a solvent in a proportion of about 5 percent by weight or less can be used.

Specific examples of solvents include alcohols, e.g., ethanol and isopropyl alcohol; ketones, e.g., methyl ethyl ketone; and aromatic compounds, e.g., xylene. These solvents can

also be used by mixing.

It is basically desirable that no solvent is contained from the viewpoint of eliminating the need for a drying step. However, in the case where a solvent is added for the purpose of adjusting the viscosity of the photosensitive paste or in the case where a solvent is added accompanying an additive when the additive or the like is added, no specific problem occurs as long as the proportion of the solvent is about 5 percent by weight or less. Even when the content of the solvent exceeds about 5 percent by weight, the operation and the effect of various preferred embodiments of the present invention is not always impaired, although the drying step is required.

In preferred embodiments of the present invention, if necessary, the photosensitive paste can also include additives, e.g., a thixotropic agent (thickener, anti-settling agent), a dispersing agent, a polymerization inhibitor (radical trapping agent), and an ultraviolet absorber (dye, pigment, HALS = hindered amine based light stabilizer).

The features of the present invention will be described below in further detail with reference to examples of various preferred embodiments thereof.

Example No. 1

<Preparation of photosensitive paste P1>

The following materials were blended and kneaded, so that photosensitive paste P1 containing no polymer was prepared.

Ag powder (average particle diameter = 2.8 μm): 75.0 percent
by weight

dipentaerythritol hexaacrylate (photosensitive monomer):
17.7 percent by weight

5 2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:
1.6 percent by weight

2,4-diethylthioxanthone: 0.5 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:
2.2 percent by weight

10 pentamethylene glycol: 3.0 percent by weight

<Formation of film by using photosensitive paste P1 and
evaluation of properties>

The photo-curing depth of the resulting photosensitive paste
15 P1 was 18.9 μm at an amount of exposure of 400 mJ/cm^2 .

As shown in Fig. 1(a), a film (photosensitive paste film) 2
having a thickness of 17.0 μm was formed on a substrate (an
alumina substrate in the present Example) 1 serving as a support
through screen printing by using this photosensitive paste P1.
20 Thereafter, the photosensitive paste film 2 was cured by
application of ultraviolet light under a condition of 400 mJ/cm^2
through a photomask 3, as shown in Fig. 1(b), and uncured
portions were removed with ethanol, as shown in Fig. 1(c), so
that a thick film pattern was produced, in which a plurality of
25 line-shaped patterns L having the same width were disposed with
spaces S therebetween. The lower limit of the pattern width of

the line-shaped patterns L was 20 μm , and the lower limit of the space width of the spaces S was 20 μm (hereafter represented by, for example, a minimum $L/S = 20/20 \mu\text{m}$).

5 The aspect ratio (a ratio of a height dimension to a base dimension (height dimension/base dimension) of a cross section of the pattern was determined from dimensions after firing. The resulting aspect ratio was 0.80.

Subsequently, a film having a thickness of 25 μm was formed on an alumina substrate by using this photosensitive paste P1
10 through screen printing, and the resulting film was cured by application of ultraviolet light at 400 mJ/cm^2 . This operation was repeated, so that a paste film having a thickness of 100 μm was formed. The Vickers hardness of this coating film measured 24.6 Hv.

15

Example No. 2

<Preparation of photosensitive paste P2>

The following materials were blended and kneaded, so that photosensitive paste P2 containing no polymer was prepared.

20 Ag powder (average particle diameter = 2.8 μm): 80.0 percent by weight

dipentaerythritol hexaacrylate (photosensitive monomer):
14.8 percent by weight

2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:
25 2.0 percent by weight

2,4-diethylthioxanthone: 0.9 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:
2.3 percent by weight

<Formation of film by using photosensitive paste P2 and
5 evaluation of properties>

The photo-curing depth of the resulting photosensitive paste
P2 was 16.2 μm at an amount of exposure of 400 mJ/cm^2 . A film
having a thickness of 16.0 μm was formed on an alumina substrate
through screen printing by using this photosensitive paste P2.
10 Thereafter, the resulting film was cured by application of
ultraviolet light under a condition of 400 mJ/cm^2 through a
photomask, and uncured portions were removed with ethanol. As a
result, the minimum L/S was 25/25 μm .

The aspect ratio of the pattern was determined from
15 dimensions after firing. The resulting aspect ratio was 0.69.

Subsequently, a film having a thickness of 25 μm was formed
on an alumina substrate by using this photosensitive paste P2
through screen printing, and the resulting film was cured by
application of ultraviolet light at 400 mJ/cm^2 . This operation
20 was repeated, so that a paste film having a thickness of 100 μm
was formed. The Vickers hardness of this coating film measured
15.2 Hv.

25 Example No. 3

<Preparation of photosensitive paste P3>

The following materials were blended and kneaded, so that photosensitive paste P3 containing no polymer was prepared.

Ag powder (average particle diameter = 2.8 μm): 85.0 percent by weight

5 dipentaerythritol hexaacrylate (photosensitive monomer): 10.9 percent by weight

2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on: 1.2 percent by weight

2,4-diethylthioxanthone: 0.4 percent by weight

10 2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1: 1.2 percent by weight

ethylcarbitol acetate: 1.3 percent by weight

<Formation of film by using photosensitive paste P3 and
15 evaluation of properties>

The photo-curing depth of the resulting photosensitive paste P3 was 12.8 μm at an amount of exposure of 400 mJ/cm^2 . A film having a thickness of 12.0 μm was formed on an alumina substrate through screen printing by using this photosensitive paste P3.
20 Thereafter, the resulting film was cured by application of ultraviolet light under a condition of 400 mJ/cm^2 through a photomask, and uncured portions were removed with ethanol. As a result, the minimum L/S was 25/25 μm .

The aspect ratio of the pattern was determined from
25 dimensions after firing. The resulting aspect ratio was 0.61.

Subsequently, a film having a thickness of 25 μm was formed

on an alumina substrate by using this photosensitive paste P3 through screen printing, and the resulting film was cured by application of ultraviolet light at 400 mJ/cm^2 . This operation was repeated, so that a paste film having a thickness of $100 \mu\text{m}$ was formed. The Vickers hardness of this coating film measured 10.6 Hv.

Example No. 4

<Preparation of photosensitive paste P4>

10 The following materials were blended and kneaded, so that photosensitive paste P4 containing no polymer was prepared.

Ag powder (average particle diameter = $2.8 \mu\text{m}$): 71.0 percent by weight

dipentaerythritol hexaacrylate (photosensitive monomer):

15 11.0 percent by weight

trimethylolpropane EO-modified (degree of polymerization $n =$

1) triacrylate (photosensitive monomer): 11.0 percent by weight

2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:

1.7 percent by weight

20 2,4-diethylthioxanthone: 1.5 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:

2.3 percent by weight

thixotropic agent: 1.5 percent by weight

25 <Formation of film by using photosensitive paste P4 and evaluation of properties>

The photo-curing depth of the resulting photosensitive paste P4 was 22.1 μm at an amount of exposure of 400 mJ/cm^2 . A film having a thickness of 20.8 μm was formed on an alumina substrate through screen printing by using this photosensitive paste P4.

5 Thereafter, the resulting film was cured by application of ultraviolet light under a condition of 400 mJ/cm^2 through a photomask, and uncured portions were removed with acetone. As a result, the minimum L/S was 25/20 μm .

The aspect ratio of the pattern was determined from
10 dimensions after firing. The resulting aspect ratio was 0.68.

Subsequently, a film having a thickness of 25 μm was formed on an alumina substrate by using this photosensitive paste P4 through screen printing, and the resulting film was cured by application of ultraviolet light at 400 mJ/cm^2 . This operation
15 was repeated, so that a paste film having a thickness of 100 μm was formed. The Vickers hardness of this coating film measured 30.2 Hv.

Example No. 5

<Preparation of photosensitive paste P5>

20 The following materials were blended and kneaded, so that photosensitive paste P5 containing no polymer was prepared.

Ag powder (average particle diameter = 2.8 μm): 75.0 percent
by weight

dipentaerythritol hexaacrylate (photosensitive monomer): 9.5
25 percent by weight

trimethylolpropane EO-modified (degree of polymerization $n =$

1) triacrylate (photosensitive monomer): 9.5 percent by weight

2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:
2.8 percent by weight

2,4-diethylthioxanthone: 0.7 percent by weight

5 2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:
2.5 percent by weight

<Formation of film by using photosensitive paste P5 and
evaluation of properties>

10 The photo-curing depth of the resulting photosensitive paste
P5 was 18.5 μm at an amount of exposure of 400 mJ/cm^2 . A film
having a thickness of 18.1 μm was formed on an alumina substrate
through screen printing by using this photosensitive paste P5.
Thereafter, the resulting film was cured by application of
15 ultraviolet light under a condition of 400 mJ/cm^2 through a
photomask, and uncured portions were removed with acetone. As a
result, the minimum L/S was 25/25 μm .

The aspect ratio of the pattern was determined from
dimensions after firing. The resulting aspect ratio was 0.62.

20 Subsequently, a film having a thickness of 25 μm was formed
on an alumina substrate by using this photosensitive paste P5
through screen printing, and the resulting film was cured by
application of ultraviolet light at 400 mJ/cm^2 . This operation
was repeated, so that a paste film having a thickness of 100 μm
25 was formed. The Vickers hardness of this coating film measured
26.5 Hv.

Example No. 6

<Preparation of photosensitive paste P6>

The following materials were blended and kneaded, so that
5 photosensitive paste P6 containing no polymer was prepared.

Ag powder (average particle diameter = $2.8\ \mu\text{m}$): 80.0 percent
by weight

dipentaerythritol hexaacrylate (photosensitive monomer): 7.6
percent by weight

10 trimethylolpropane EO-modified (degree of polymerization $n =$
1) triacrylate (photosensitive monomer): 7.6 percent by weight

2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:
1.5 percent by weight

2,4-diethylthioxanthone: 0.6 percent by weight

15 2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:
2.0 percent by weight

pentamethylene glycol: 0.7 percent by weight

<Formation of film by using photosensitive paste P6 and
20 evaluation of properties>

The photo-curing depth of the resulting photosensitive paste
P6 was $17.0\ \mu\text{m}$ at an amount of exposure of $400\ \text{mJ}/\text{cm}^2$. A film
having a thickness of $16.8\ \mu\text{m}$ was formed on an alumina substrate
through screen printing by using this photosensitive paste P6.
25 Thereafter, the resulting film was cured by application of
ultraviolet light under a condition of $400\ \text{mJ}/\text{cm}^2$ through a

photomask, and uncured portions were removed with acetone. As a result, the minimum L/S was 30/30 μm .

The aspect ratio of the pattern was determined from dimensions after firing. The resulting aspect ratio was 0.55.

5 Subsequently, a film having a thickness of 25 μm was formed on an alumina substrate by using this photosensitive paste P6 through screen printing, and the resulting film was cured by application of ultraviolet light at 400 mJ/cm^2 . This operation was repeated, so that a paste film having a thickness of 100 μm
10 was formed. The Vickers hardness of this coating film measured 17.1 Hv.

Example No. 7

<Preparation of photosensitive paste P7>

15 The following materials were blended and kneaded, so that photosensitive paste P7 containing no polymer was prepared.

Ag powder (average particle diameter = 2.8 μm): 80.0 percent by weight

Si-B based glass powder (average particle diameter = 1.5
20 μm): 2.4 percent by weight

dipentaerythritol hexaacrylate (photosensitive monomer):
15.0 percent by weight

2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:
1.5 percent by weight

25 2,4-diethylthioxanthone: 0.6 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:

0.5 percent by weight

<Formation of film by using photosensitive paste P7 and
evaluation of properties>

5 The photo-curing depth of the resulting photosensitive paste
P7 was 15.2 μm at an amount of exposure of 400 mJ/cm^2 .

As shown in Fig. 2(a), a film (photosensitive paste film) 2
having a thickness of 14.7 μm was formed on a PET film 5 serving
as a support through screen printing by using this photosensitive
10 paste P7. Thereafter, the resulting film 2 was cured by
application of ultraviolet light under a condition of 400 mJ/cm^2
through a photomask, and uncured portions were removed with
ethanol, as shown in Fig. 2(b). As a result, the minimum ratio
of the line-shaped pattern L to the space S (L/S) was 25/30 μm .

15 Subsequently, the pattern (thick film pattern) L disposed on
this PET film 5 was turned upside down and, as shown in Fig. 2(c),
was pressed and transferred to a green sheet 6 by using a
thermocompression bonding device under the condition of 60°C, 0.5
MPa, and 60 seconds, so that a pattern (thick film pattern) L was
20 formed on the green sheet 6, as shown in Fig. 2(d). This pattern
L was fired and the width and the thickness of the pattern were
observed with a laser microscope. The resulting aspect ratio was
0.51.

A film having a thickness of 25 μm was formed on an alumina
25 substrate by using this photosensitive paste P7 through screen
printing, and the resulting film was cured by application of

ultraviolet light at 400 mJ/cm^2 . This operation was repeated, so that a paste film having a thickness of $100 \text{ }\mu\text{m}$ was formed. The Vickers hardness of this coating film measured 14.8 Hv .

5 Example No. 8

<Preparation of photosensitive paste P8>

The following materials were blended and kneaded, so that photosensitive paste P8 containing no polymer was prepared.

Ag powder (average particle diameter = $2.8 \text{ }\mu\text{m}$): 56.3 percent
10 by weight

Al_2O_3 -coated Ag (average particle diameter = $2.0 \text{ }\mu\text{m}$): 18.8
percent by weight

Si-B based glass powder (average particle diameter = $1.5 \text{ }\mu\text{m}$): 2.4 percent by weight

15 dipentaerythritol hexaacrylate (photosensitive monomer):
16.5 percent by weight

2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:
1.5 percent by weight

2,4-diethylthioxanthone: 0.9 percent by weight

20 2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:
2.3 percent by weight

dipropylene glycol monomethyl ether: 1.3 percent by weight

<Formation of film by using photosensitive paste P8 and
evaluation of properties>

25 The photo-curing depth of the resulting photosensitive paste
P8 was $13.9 \text{ }\mu\text{m}$ at an amount of exposure of 400 mJ/cm^2 . A film

having a thickness of 13.0 μm was formed on a PET film serving as a support through screen printing by using this photosensitive paste P8. Thereafter, the resulting film was cured by application of ultraviolet light under a condition of 400 mJ/cm^2 through a photomask, and uncured portions were removed with ethanol. As a result, the minimum L/S was 25/30 μm .

Subsequently, the pattern disposed on this PET film was turned upside down, and was pressed and transferred to a green sheet by using a thermocompression bonding device under the condition of 60°C, 0.5 MPa, and 60 seconds. The resulting pattern was fired and the width and the thickness of the pattern were observed with a laser microscope. The resulting aspect ratio was 0.45.

A film having a thickness of 25 μm was formed on an alumina substrate by using this photosensitive paste P8 through screen printing, and the resulting film was cured by application of ultraviolet light at 400 mJ/cm^2 . This operation was repeated, so that a paste film having a thickness of 100 μm was formed. The Vickers hardness of this coating film measured 15.4 Hv.

Example No. 9

<Preparation of photosensitive paste P9>

The following materials were blended and kneaded, so that photosensitive paste P9 containing no polymer was prepared.

Cu powder (average particle diameter = 2.5 μm): 77.0 percent by weight

dipentaerythritol hexaacrylate (photosensitive monomer):

14.0 percent by weight

2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:

1.0 percent by weight

2,4-diethylthioxanthone: 0.4 percent by weight

5 2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:

1.6 percent by weight

dipropylene glycol monomethyl ether: 3.0 percent by weight

pentamethylene glycol: 3.0 percent by weight

10 <Formation of film by using photosensitive paste P9 and
evaluation of properties>

The photo-curing depth of the resulting photosensitive paste
P9 was 15.8 μm at an amount of exposure of 400 mJ/cm^2 . A film
having a thickness of 15.1 μm was formed on an alumina substrate
15 through screen printing by using this photosensitive paste P9.
Thereafter, the resulting film was cured by application of
ultraviolet light under a condition of 400 mJ/cm^2 through a
photomask, and uncured portions were removed with ethanol. As a
result, the minimum L/S was 30/30 μm .

20 The aspect ratio of the pattern was determined from
dimensions after firing. The resulting aspect ratio was 0.59.

Subsequently, a film having a thickness of 25 μm was formed
on an alumina substrate by using this photosensitive paste P9
through screen printing, and the resulting film was cured by
25 application of ultraviolet light at 400 mJ/cm^2 . This operation
was repeated, so that a paste film having a thickness of 100 μm

was formed. The Vickers hardness of this coating film measured 17.8 Hv.

Example No. 10

5 <Preparation of photosensitive paste P10>

The following materials were blended and kneaded, so that photosensitive paste P10 containing no polymer was prepared.

Cu powder (average particle diameter = 2.5 μm): 80.0 percent by weight

10 dipentaerythritol hexaacrylate (photosensitive monomer): 14.0 percent by weight

2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on: 1.8 percent by weight

2,4-diethylthioxanthone: 0.9 percent by weight

15 2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1: 2.1 percent by weight

di-n-butyl phthalate: 1.2 percent by weight

20 <Formation of film by using photosensitive paste P10 and evaluation of properties>

The photo-curing depth of the resulting photosensitive paste P10 was 14.8 μm at an amount of exposure of 400 mJ/cm^2 . A film having a thickness of 13.8 μm was formed on an alumina substrate through screen printing by using this photosensitive paste P10.

25 Thereafter, the resulting film was cured by application of ultraviolet light under a condition of 400 mJ/cm^2 through a

photomask, and uncured portions were removed with ethanol. As a result, the minimum L/S was 25/25 μm .

The aspect ratio of the pattern was determined from dimensions after firing. The resulting aspect ratio was 0.53.

5 Subsequently, a film having a thickness of 25 μm was formed on an alumina substrate by using this photosensitive paste P10 through screen printing, and the resulting film was cured by application of ultraviolet light at 400 mJ/cm². This operation was repeated, so that a paste film having a thickness of 100 μm
10 was formed. The Vickers hardness of this coating film measured 16.9 Hv.

Example No. 11

<Preparation of photosensitive paste P11>

15 The following materials were blended and kneaded, so that photosensitive paste P11 containing no polymer was prepared.

AgPd powder (average particle diameter = 2.0 μm): 80.0 percent by weight

dipentaerythritol hexaacrylate (photosensitive monomer):
20 14.0 percent by weight

2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:
3.0 percent by weight

2,4-diethylthioxanthone: 0.9 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:
25 2.1 percent by weight

<Formation of film by using photosensitive paste P11 and
evaluation of properties>

The photo-curing depth of the resulting photosensitive paste
P11 was 14.1 μm at an amount of exposure of 400 mJ/cm^2 . A film
5 having a thickness of 14.0 μm was formed on an alumina substrate
through screen printing by using this photosensitive paste P11.
Thereafter, the resulting film was cured by application of
ultraviolet light under a condition of 400 mJ/cm^2 through a
photomask, and uncured portions were removed with ethanol. As a
10 result, the minimum L/S was 20/20 μm .

The aspect ratio of the pattern was determined from
dimensions after firing. The resulting aspect ratio was 0.70.

Subsequently, a film having a thickness of 25 μm was formed
on an alumina substrate by using this photosensitive paste P11
15 through screen printing, and the resulting film was cured by
application of ultraviolet light at 400 mJ/cm^2 . This operation
was repeated, so that a paste film having a thickness of 100 μm
was formed. The Vickers hardness of this coating film measured
15.7 Hv.

20

Example No. 12

<Preparation of photosensitive paste P12>

The following materials were blended and kneaded, so that
photosensitive paste P12 containing no polymer was prepared.

25 Ag powder (average particle diameter = 3.0 μm): 75.0 percent
by weight

trimethylolpropane triacrylate (not modified by ethylene oxide) (photosensitive monomer): 16.5 percent by weight

2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:
5.0 percent by weight

5 2,4-diethylthioxanthone: 2.0 percent by weight

thixotropic agent: 1.5 percent by weight

<Formation of film by using photosensitive paste P12 and
evaluation of properties>

10 The photo-curing depth of the resulting photosensitive paste
P12 was 17.1 μm at an amount of exposure of 400 mJ/cm^2 . A film
having a thickness of 17.0 μm was formed on an alumina substrate
through screen printing by using this photosensitive paste P12.
Thereafter, the resulting film was cured by application of
15 ultraviolet light under a condition of 400 mJ/cm^2 through a
photomask, and uncured portions were removed with ethanol. As a
result, the minimum L/S was 30/30 μm .

The aspect ratio of the pattern was determined from
dimensions after firing. The resulting aspect ratio was 0.61.

20 Subsequently, a film having a thickness of 25 μm was formed
on an alumina substrate by using this photosensitive paste P12
through screen printing, and the resulting film was cured by
application of ultraviolet light at 400 mJ/cm^2 . This operation
was repeated, so that a paste film having a thickness of 100 μm
25 was formed. The Vickers hardness of this coating film measured
27.5 Hv.

Example No. 13

<Preparation of photosensitive paste P13>

The following materials were blended and kneaded, so that
5 photosensitive paste P13 containing a polymer within the scope of
the present invention was prepared.

Ag powder (average particle diameter = 2.8 μm): 75.0 percent
by weight

acrylic copolymer (polymer): 0.5 percent by weight

10 trimethylolpropane EO-modified (degree of polymerization $n =$
1) triacrylate (photosensitive monomer): 14.5 percent by weight
(photosensitive monomer/(photosensitive monomer + polymer) =
14.5/(14.5 + 0.5) = 0.97)

benzyl dimethyl ketal: 2.0 percent by weight

15 bis(2,4,6-trimethylbenzoyl)-phenylphosphine oxide: 2.0
percent by weight

dipropylene glycol monomethyl ether: 5.0 percent by weight

thixotropic agent: 1.0 percent by weight

20 <Formation of film by using photosensitive paste P13 and
evaluation of properties>

The photo-curing depth of the resulting photosensitive paste
P13 was 16.7 μm at an amount of exposure of 400 mJ/cm^2 . A film
having a thickness of 16.5 μm was formed on an alumina substrate
25 through screen printing by using this photosensitive paste P13.
Thereafter, the resulting film was cured by application of

ultraviolet light under a condition of 400 mJ/cm^2 through a photomask, and uncured portions were removed with ethanol. As a result, the minimum L/S was $25/25 \text{ }\mu\text{m}$.

The aspect ratio of the pattern was determined from
5 dimensions after firing. The resulting aspect ratio was 0.68.

Subsequently, a film having a thickness of $25 \text{ }\mu\text{m}$ was formed on an alumina substrate by using this photosensitive paste P13 through screen printing, and the resulting film was cured by application of ultraviolet light at 400 mJ/cm^2 . This operation
10 was repeated, so that a paste film having a thickness of $100 \text{ }\mu\text{m}$ was formed. The Vickers hardness of this coating film measured 19.9 Hv .

Example No. 14

15 <Preparation of photosensitive paste P14>

The following materials were blended and kneaded, so that photosensitive paste P14 containing a polymer within the scope of the present invention was prepared.

Ag powder (average particle diameter = $2.8 \text{ }\mu\text{m}$): 75.0 percent
20 by weight

acrylic copolymer (polymer): 1.0 percent by weight

dipentaerythritol hexaacrylate (photosensitive monomer):
17.5 percent by weight

(photosensitive monomer/(photosensitive monomer + polymer) =
25 $17.5/(17.5 + 1.0) = 0.95$)

1-hydroxy-cyclohexyl-phenyl-ketone: 2.5 percent by weight

bis(2,4,6-trimethylbenzoyl)-phenylphosphine oxide: 3.0
percent by weight

dipropylene glycol monomethyl ether: 1.0 percent by weight

5 <Formation of film by using photosensitive paste P14 and
evaluation of properties>

The photo-curing depth of the resulting photosensitive paste
P14 was 16.0 μm at an amount of exposure of 400 mJ/cm^2 . A film
having a thickness of 15.8 μm was formed on an alumina substrate
10 through screen printing by using this photosensitive paste P14.
Thereafter, the resulting film was cured by application of
ultraviolet light under a condition of 400 mJ/cm^2 through a
photomask, and uncured portions were removed with ethanol. As a
result, the minimum L/S was 25/25 μm .

15 The aspect ratio of the pattern was determined from
dimensions after firing. The resulting aspect ratio was 0.62.

Subsequently, a film having a thickness of 25 μm was formed
on an alumina substrate by using this photosensitive paste P14
through screen printing, and the resulting film was cured by
20 application of ultraviolet light at 400 mJ/cm^2 . This operation
was repeated, so that a paste film having a thickness of 100 μm
was formed. The Vickers hardness of this coating film measured
18.5 Hv.

25 Example No. 15

<Preparation of photosensitive paste P15>

The following materials were blended and kneaded, so that photosensitive paste P15 containing a polymer within the scope of the present invention was prepared.

Ag powder (average particle diameter = 2.8 μm): 75.0 percent
5 by weight

acrylic copolymer (polymer): 1.0 percent by weight

dipentaerythritol hexaacrylate (photosensitive monomer): 9.0
percent by weight

(photosensitive monomer/(photosensitive monomer + polymer) =
10 $9.0/(9.0 + 1.0) = 0.90$)

1-hydroxy-cyclohexyl-phenyl-ketone: 3.5 percent by weight

bis(2,4,6-trimethylbenzoyl)-phenylphosphine oxide: 5.5
percent by weight

dipropylene glycol monomethyl ether: 4.0 percent by weight

15 thixotropic agent: 2.0 percent by weight

<Formation of film by using photosensitive paste P15 and
evaluation of properties>

The photo-curing depth of the resulting photosensitive paste
20 P15 was 15.6 μm at an amount of exposure of 400 mJ/cm^2 . A film
having a thickness of 15.1 μm was formed on an alumina substrate
through screen printing by using this photosensitive paste P15.
Thereafter, the resulting film was cured by application of
ultraviolet light under a condition of 400 mJ/cm^2 through a
25 photomask, and uncured portions were removed with ethanol. As a
result, the minimum L/S was 25/25 μm .

The aspect ratio of the pattern was determined from dimensions after firing. The resulting aspect ratio was 0.60.

Subsequently, a film having a thickness of 25 μm was formed on an alumina substrate by using this photosensitive paste P15 through screen printing, and the resulting film was cured by application of ultraviolet light at 400 mJ/cm^2 . This operation was repeated, so that a paste film having a thickness of 100 μm was formed. The Vickers hardness of this coating film measured 18.4 Hv.

Example No. 16

<Preparation of photosensitive paste P16>

The following materials were blended and kneaded, so that photosensitive paste P16 containing a polymer within the scope of the present invention was prepared.

Ag powder (average particle diameter = 2.8 μm): 75.0 percent by weight

acrylic copolymer (polymer): 2.0 percent by weight

dipentaerythritol hexaacrylate (photosensitive monomer):

12.5 percent by weight

$(\text{photosensitive monomer}/(\text{photosensitive monomer} + \text{polymer}) = 12.5/(12.5 + 2.0) = 0.86)$

1-hydroxy-cyclohexyl-phenyl-ketone: 2.0 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:

3.2 percent by weight

dipropylene glycol monomethyl ether: 3.8 percent by weight

thixotropic agent: 1.5 percent by weight

<Formation of film by using photosensitive paste P16 and
evaluation of properties>

5 The photo-curing depth of the resulting photosensitive paste
P16 was 14.2 μm at an amount of exposure of 400 mJ/cm^2 . A film
having a thickness of 14.0 μm was formed on an alumina substrate
through screen printing by using this photosensitive paste P16.
Thereafter, the resulting film was cured by application of
10 ultraviolet light under a condition of 400 mJ/cm^2 through a
photomask, and uncured portions were removed with ethanol. As a
result, the minimum L/S was 30/25 μm .

The aspect ratio of the pattern was determined from
dimensions after firing. The resulting aspect ratio was 0.48.

15 Subsequently, a film having a thickness of 25 μm was formed
on an alumina substrate by using this photosensitive paste P16
through screen printing, and the resulting film was cured by
application of ultraviolet light at 400 mJ/cm^2 . This operation
was repeated, so that a paste film having a thickness of 100 μm
20 was formed. The Vickers hardness of this coating film measured
18.0 Hv.

Example No. 17

<Preparation of photosensitive paste P17>

25 The following materials were blended and kneaded, so that
photosensitive paste P17 containing no polymer was prepared.

Ag powder (average particle diameter = 3.0 μm): 75.0 percent
by weight

trimethylolpropane EO-modified (degree of polymerization n =
1) triacrylate (photosensitive monomer): 16.0 percent by weight

5 2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:
4.5 percent by weight

2,4-diethylthioxanthone: 1.0 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:
1.5 percent by weight

10 thixotropic agent: 2.0 percent by weight

<Formation of film by using photosensitive paste P17 and
evaluation of properties>

The photo-curing depth of the resulting photosensitive paste
15 P17 was 12.5 μm at an amount of exposure of 400 mJ/cm^2 . A film
having a thickness of 11.5 μm was formed on an alumina substrate
through screen printing by using this photosensitive paste P17.
Thereafter, the resulting film was cured by application of
ultraviolet light under a condition of 400 mJ/cm^2 through a
20 photomask, and uncured portions were removed with ethanol. As a
result, the minimum L/S was 30/25 μm .

The aspect ratio of the pattern was determined from
dimensions after firing. The resulting aspect ratio was 0.55.

Subsequently, a film having a thickness of 25 μm was formed
25 on an alumina substrate by using this photosensitive paste P17
through screen printing, and the resulting film was cured by

application of ultraviolet light at 400 mJ/cm^2 . This operation was repeated, so that a paste film having a thickness of $100 \text{ }\mu\text{m}$ was formed. The Vickers hardness of this coating film measured 15.8 Hv .

5

Example No. 18

<Preparation of photosensitive paste P18>

The following materials were blended and kneaded, so that photosensitive paste P18 containing no polymer was prepared.

10 Ag powder (average particle diameter = $3.0 \text{ }\mu\text{m}$): 75.0 percent by weight

triallyl isocyanurate (photosensitive monomer): 17.5 percent by weight

15 2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:
2.5 percent by weight

2,4-diethylthioxanthone: 0.9 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:
2.5 percent by weight

thixotropic agent: 1.6 percent by weight

20

<Formation of film by using photosensitive paste P18 and evaluation of properties>

The photo-curing depth of the resulting photosensitive paste P18 was $13.8 \text{ }\mu\text{m}$ at an amount of exposure of 400 mJ/cm^2 . A film
25 having a thickness of $12.5 \text{ }\mu\text{m}$ was formed on an alumina substrate through screen printing by using this photosensitive paste P18.

Thereafter, the resulting film was cured by application of ultraviolet light under a condition of 400 mJ/cm^2 through a photomask, and uncured portions were removed with ethanol. As a result, the minimum L/S was $35/35 \text{ }\mu\text{m}$.

5 The aspect ratio of the pattern was determined from dimensions after firing. The resulting aspect ratio was 0.35.

Subsequently, a film having a thickness of $25 \text{ }\mu\text{m}$ was formed on an alumina substrate by using this photosensitive paste P18 through screen printing, and the resulting film was cured by
10 application of ultraviolet light at 400 mJ/cm^2 . This operation was repeated, so that a paste film having a thickness of $100 \text{ }\mu\text{m}$ was formed. The Vickers hardness of this coating film measured 14.3 Hv .

15 Example No. 19

<Preparation of photosensitive paste P19>

The following materials were blended and kneaded, so that photosensitive paste P19 containing no polymer was prepared.

Ag powder (average particle diameter = $3.0 \text{ }\mu\text{m}$): 75.0 percent
20 by weight

trimethylolpropane EO-modified (degree of polymerization $n = 3$) triacrylate (photosensitive monomer): 18.0 percent by weight

benzyl dimethyl ketal: 2.5 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:
25 2.5 percent by weight

thixotropic agent: 2.0 percent by weight

<Formation of film by using photosensitive paste P19 and
evaluation of properties>

The photo-curing depth of the resulting photosensitive paste
5 P19 was 11.3 μm at an amount of exposure of 400 mJ/cm^2 . A film
having a thickness of 10.0 μm was formed on an alumina substrate
through screen printing by using this photosensitive paste P19.
Thereafter, the resulting film was cured by application of
ultraviolet light under a condition of 400 mJ/cm^2 through a
10 photomask, and uncured portions were removed with ethanol. As a
result, the minimum L/S was 35/30 μm .

The aspect ratio of the pattern was determined from
dimensions after firing. The resulting aspect ratio was 0.30.

Subsequently, a film having a thickness of 25 μm was formed
15 on an alumina substrate by using this photosensitive paste P19
through screen printing, and the resulting film was cured by
application of ultraviolet light at 400 mJ/cm^2 . This operation
was repeated, so that a paste film having a thickness of 100 μm
was formed. The Vickers hardness of this coating film measured
20 13.2 Hv.

Example No. 20

<Preparation of photosensitive paste P20>

The following materials were blended and kneaded, so that
25 photosensitive paste P20 containing no polymer was prepared.

Ag powder (average particle diameter = 3.0 μm): 75.0 percent

by weight

trimethylolpropane EO-modified (degree of polymerization $n = 4$) triacrylate (photosensitive monomer): 18.5 percent by weight

2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:

5 2.5 percent by weight

2,4-diethylthioxanthone: 0.9 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:
1.6 percent by weight

thixotropic agent: 1.5 percent by weight

10

<Formation of film by using photosensitive paste P20 and
evaluation of properties>

The photo-curing depth of the resulting photosensitive paste
P20 was 11.0 μm at an amount of exposure of 400 mJ/cm^2 . A film
15 having a thickness of 9.5 μm was formed on an alumina substrate
through screen printing by using this photosensitive paste P20.
Thereafter, the resulting film was cured by application of
ultraviolet light under a condition of 400 mJ/cm^2 through a
photomask, and uncured portions were removed with ethanol. As a
20 result, the minimum L/S was 40/30 μm .

The aspect ratio of the pattern was determined from
dimensions after firing. The resulting aspect ratio was 0.29.

Subsequently, a film having a thickness of 25 μm was formed
on an alumina substrate by using this photosensitive paste P20
25 through screen printing, and the resulting film was cured by
application of ultraviolet light at 400 mJ/cm^2 . This operation

was repeated, so that a paste film having a thickness of 100 μm was formed. The Vickers hardness of this coating film measured 13.1 Hv.

5 Example No. 21

<Preparation of photosensitive paste P21>

The following materials were blended and kneaded, so that photosensitive paste P21 containing no polymer was prepared.

Ag powder (average particle diameter = 2.8 μm): 80.0 percent
10 by weight

dipentaerythritol hexaacrylate (photosensitive monomer):
13.2 percent by weight

2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:
2.0 percent by weight

15 2,4-diethylthioxanthone: 0.9 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:
2.3 percent by weight

ultraviolet absorber (anthraquinone based dye): 1.6 percent
by weight

20

<Formation of film by using photosensitive paste P21 and
evaluation of properties>

The photo-curing depth of the resulting photosensitive paste P21 was 15.5 μm at an amount of exposure of 400 mJ/cm^2 . A film
25 having a thickness of 14.8 μm was formed on an alumina substrate through screen printing by using this photosensitive paste P21.

Thereafter, the resulting film was cured by application of ultraviolet light under a condition of 400 mJ/cm^2 through a photomask, and uncured portions were removed with ethanol. As a result, the minimum L/S was $25/20 \text{ }\mu\text{m}$.

5 The aspect ratio of the pattern was determined from dimensions after firing. The resulting aspect ratio was 0.65.

Subsequently, a film having a thickness of $25 \text{ }\mu\text{m}$ was formed on an alumina substrate by using this photosensitive paste P21 through screen printing, and the resulting film was cured by
10 application of ultraviolet light at 400 mJ/cm^2 . This operation was repeated, so that a paste film having a thickness of $100 \text{ }\mu\text{m}$ was formed. The Vickers hardness of this coating film measured 15.1 Hv .

15 Comparative Example No. 1

<Preparation of photosensitive paste P01>

The following materials were blended and kneaded, so that photosensitive paste P01 containing a polymer outside of the scope of the present invention was prepared.

20 Ag powder (average particle diameter = $2.8 \text{ }\mu\text{m}$): 75.0 percent by weight

acrylic copolymer (polymer): 3.0 percent by weight

dipentaerythritol hexaacrylate (photosensitive monomer):
13.0 percent by weight

25 $(\text{photosensitive monomer}/(\text{photosensitive monomer} + \text{polymer})) =$
 $13.0/(13.0 + 3.0) = 0.81)$

2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:

2.0 percent by weight

2,4-diethylthioxanthone: 0.5 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:

5 3.0 percent by weight

dipropylene glycol monomethyl ether: 2.0 percent by weight

thixotropic agent: 1.5 percent by weight

<Formation of film by using photosensitive paste P01 and
evaluation of properties>

10 The photo-curing depth of the resulting photosensitive paste
P01 was 9.6 μm at an amount of exposure of 400 mJ/cm^2 . A film
having a thickness of 9.6 μm was formed on an alumina substrate
through screen printing by using this photosensitive paste P01.
Thereafter, the resulting film was cured by application of
15 ultraviolet light under a condition of 400 mJ/cm^2 through a
photomask, and uncured portions were removed with ethanol. As a
result, the minimum L/S was 30/30 μm .

The aspect ratio of the pattern was determined from
dimensions after firing. The resulting aspect ratio was 0.32.

20 Subsequently, a film having a thickness of 25 μm was formed
on an alumina substrate by using this photosensitive paste P01
through screen printing, and the resulting film was cured by
application of ultraviolet light at 400 mJ/cm^2 . This operation
was repeated, so that a paste film having a thickness of 100 μm
25 was formed. The Vickers hardness of this coating film measured
17.3 Hv.

Comparative Example No. 2

<Preparation of photosensitive paste P02>

5 The following materials were blended and kneaded, so that
photosensitive paste P02 containing a polymer outside of the
scope of the present invention was prepared.

Ag powder (average particle diameter = 2.8 μm): 75.0 percent
by weight

acrylic copolymer (polymer): 4.0 percent by weight

10 dipentaerythritol hydroxypentaacrylate (photosensitive
monomer): 11.5 percent by weight

(photosensitive monomer/(photosensitive monomer + polymer) =
11.5/(11.5 + 4.0) = 0.74)

15 2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:
2.5 percent by weight

2,4-diethylthioxanthone: 0.5 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:
1.0 percent by weight

dipropylene glycol monomethyl ether: 3.5 percent by weight

20 thixotropic agent: 2.0 percent by weight

<Formation of film by using photosensitive paste P02 and
evaluation of properties>

25 The photo-curing depth of the resulting photosensitive paste
P02 was 6.7 μm at an amount of exposure of 400 mJ/cm^2 . A film

having a thickness of 6.7 μm was formed on an alumina substrate through screen printing by using this photosensitive paste P02. Thereafter, the resulting film was cured by application of ultraviolet light under a condition of 400 mJ/cm^2 through a photomask, and uncured portions were removed with a 0.5 percent by weight sodium carbonate aqueous solution. As a result, the minimum L/S was 30/30 μm .

The aspect ratio of the pattern was determined from dimensions after firing. The resulting aspect ratio was 0.27.

Subsequently, a film having a thickness of 25 μm was formed on an alumina substrate by using this photosensitive paste P02 through screen printing, and the resulting film was cured by application of ultraviolet light at 400 mJ/cm^2 . This operation was repeated, so that a paste film having a thickness of 100 μm was formed. The Vickers hardness of this coating film measured 15.4 Hv.

Comparative Example No. 3

<Preparation of photosensitive paste P03>

The following materials were blended and kneaded, so that photosensitive paste P03 containing a polymer outside of the scope of the present invention was prepared.

Ag powder (average particle diameter = 2.8 μm): 74.0 percent by weight

acrylic polymer (polymer): 6.2 percent by weight

trimethylolpropane EO-modified (degree of polymerization $n =$

1) triacrylate (photosensitive monomer): 6.0 percent by weight
(photosensitive monomer/(photosensitive monomer + polymer) =
6.0/(6.0 + 6.2) = 0.49)

2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:

5 0.6 percent by weight

2,4-diethylthioxanthone: 0.2 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:

0.9 percent by weight

dipropylene glycol monomethyl ether: 11.6 percent by weight

10 thixotropic agent: 0.5 percent by weight

<Formation of film by using photosensitive paste P03 and
evaluation of properties>

The photo-curing depth of the resulting photosensitive paste
15 P03 was 9.1 μm at an amount of exposure of 400 mJ/cm^2 . A film
having a thickness of 8.5 μm was formed on an alumina substrate
through screen printing by using this photosensitive paste P03.
Thereafter, the resulting film was cured by application of
ultraviolet light under a condition of 400 mJ/cm^2 through a
20 photomask, and uncured portions were removed with a 0.5 percent
by weight sodium carbonate aqueous solution. As a result, the
minimum L/S was 25/25 μm .

The aspect ratio of the pattern was determined from
dimensions after firing. The resulting aspect ratio was 0.43.

25 Subsequently, a film having a thickness of 25 μm was formed
on an alumina substrate by using this photosensitive paste P03

through screen printing, and the resulting film was cured by application of ultraviolet light at 400 mJ/cm². This operation was repeated, so that a paste film having a thickness of 100 μm was formed. The Vickers hardness of this coating film measured

5 18.8 Hv.

Comparative Example No. 4

<Preparation of photosensitive paste P04>

The following materials were blended and kneaded, so that
10 photosensitive paste P04 containing a polymer outside of the scope of the present invention was prepared.

Ag powder (average particle diameter = 2.8 μm): 77.0 percent
by weight

acrylic polymer (polymer): 5.5 percent by weight

15 trimethylolpropane EO-modified (degree of polymerization n =

1) triacrylate (photosensitive monomer): 6.2 percent by weight

(photosensitive monomer/(photosensitive monomer + polymer) =
6.2/(6.2 + 5.5) = 0.53)

2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:

20 1.0 percent by weight

2,4-diethylthioxanthone: 0.2 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:

0.4 percent by weight

pentamethylene glycol: 1.2 percent by weight

25 dipropylene glycol monomethyl ether: 8.5 percent by weight

<Formation of film by using photosensitive paste P04 and evaluation of properties>

The photo-curing depth of the resulting photosensitive paste P04 was 7.2 μm at an amount of exposure of 400 mJ/cm^2 . A film having a thickness of 7.0 μm was formed on an alumina substrate through screen printing by using this photosensitive paste P04. Thereafter, the resulting film was cured by application of ultraviolet light under a condition of 400 mJ/cm^2 through a photomask, and uncured portions were removed with a 0.5 percent by weight sodium carbonate aqueous solution. As a result, the minimum L/S was 30/25 μm .

The aspect ratio of the pattern was determined from dimensions after firing. The resulting aspect ratio was 0.31.

Subsequently, a film having a thickness of 25 μm was formed on an alumina substrate by using this photosensitive paste P04 through screen printing, and the resulting film was cured by application of ultraviolet light at 400 mJ/cm^2 . This operation was repeated, so that a paste film having a thickness of 100 μm was formed. The Vickers hardness of this coating film measured 12.7 Hv.

Comparative example No. 5

<Preparation of photosensitive paste P05>

The following materials were blended and kneaded, so that photosensitive paste P05 containing a polymer outside of the scope of the present invention was prepared.

Ag powder (average particle diameter = 2.8 μm): 80 percent
by weight

Si-B based glass powder (average particle diameter = 1.5
 μm): 2.4 percent by weight

5 acrylic polymer (polymer): 4.1 percent by weight

trimethylolpropane EO-modified (degree of polymerization $n =$
1) triacrylate (photosensitive monomer): 2.8 percent by weight
(photosensitive monomer/(photosensitive monomer + polymer) =
2.8/(2.8 + 4.1) = 0.41)

10 2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:
1.8 percent by weight

2,4-diethylthioxanthone: 0.3 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:
1.1 percent by weight

15 ethylcarbitol acetate: 7.5 percent by weight

<Formation of film by using photosensitive paste P05 and
evaluation of properties>

The photo-curing depth of the resulting photosensitive paste
20 P05 was 7.0 μm at an amount of exposure of 400 mJ/cm^2 . A film
having a thickness of 7.0 μm was formed on a PET film through
screen printing by using this photosensitive paste P05.

Thereafter, the resulting film was cured by application of
ultraviolet light under a condition of 400 mJ/cm^2 through a
25 photomask, and uncured portions were removed with a 0.5 percent
by weight sodium carbonate aqueous solution. As a result, the

minimum L/S was 30/30 μm .

Subsequently, the pattern disposed on this PET film was turned upside down, and was pressed and transferred to a green sheet by using a thermocompression bonding device under the condition of 60°C, 0.5 MPa, and 60 seconds. The resulting pattern was fired and the width and the thickness of the pattern were observed with a laser microscope. The resulting aspect ratio was 0.33.

A film having a thickness of 25 μm was formed on an alumina substrate by using this photosensitive paste P05 through screen printing, and the resulting film was cured by application of ultraviolet light at 400 mJ/cm². This operation was repeated, so that a paste film having a thickness of 100 μm was formed. The Vickers hardness of this coating film measured 8.1 Hv.

15

Comparative Example No. 6

<Preparation of photosensitive paste P06>

The following materials were blended and kneaded, so that photosensitive paste P06 containing a polymer outside of the scope of the present invention was prepared.

20 Cu powder (average particle diameter = 2.5 μm): 80 percent by weight

acrylic polymer (polymer): 5.6 percent by weight

trimethylolpropane EO-modified (degree of polymerization n =

25 1) triacrylate (photosensitive monomer): 3.8 percent by weight

(photosensitive monomer/(photosensitive monomer + polymer) =

$$3.8/(3.8 + 5.6) = 0.40)$$

2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:

1.0 percent by weight

2,4-diethylthioxanthone: 0.3 percent by weight

5 2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:

1.6 percent by weight

dipropylene glycol monomethyl ether: 6.9 percent by weight

dibutyl phthalate: 0.8 percent by weight

10 <Formation of film by using photosensitive paste P06 and
evaluation of properties>

The photo-curing depth of the resulting photosensitive paste
P06 was 7.9 μm at an amount of exposure of 400 mJ/cm^2 . A film
having a thickness of 7.1 μm was formed on a PET film through
15 screen printing by using this photosensitive paste P06.

Thereafter, the resulting film was cured by application of
ultraviolet light under a condition of 400 mJ/cm^2 through a
photomask, and uncured portions were removed with a 0.5 percent
by weight sodium carbonate aqueous solution. As a result, the
20 minimum L/S was 30/30 μm .

Subsequently, the pattern disposed on this PET film was
turned upside down, and was pressed and transferred to a green
sheet by using a thermocompression bonding device under the
condition of 60°C, 0.5 MPa, and 60 seconds. The resulting
25 pattern was fired and the width and the thickness of the pattern
were observed with a laser microscope. The resulting aspect

ratio was 0.20.

A film having a thickness of 25 μm was formed on an alumina substrate by using this photosensitive paste P06 through screen printing, and the resulting film was cured by application of
5 ultraviolet light at 400 mJ/cm^2 . This operation was repeated, so that a paste film having a thickness of 100 μm was formed. The Vickers hardness of this coating film measured 12.7 Hv.

Comparative Example No. 7

10 <Preparation of photosensitive paste P07>

The following materials were blended and kneaded, so that photosensitive paste P07 containing a polymer outside of the scope of the present invention was prepared.

15 Cu powder (average particle diameter = 2.5 μm): 80 percent by weight

Si-B based glass powder (average particle diameter = 1.5 μm): 0.4 percent by weight

acrylic polymer (polymer): 7.8 percent by weight

20 trimethylolpropane EO-modified (degree of polymerization $n = 1$) triacrylate (photosensitive monomer): 2.8 percent by weight
(photosensitive monomer/(photosensitive monomer + polymer) = $2.8/(2.8 + 7.8) = 0.26$)

2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:
1.0 percent by weight 2,4-diethylthioxanthone: 0.3 percent by
25 weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:

0.5 percent by weight

dipropylene glycol monomethyl ether: 7.2 percent by weight

<Formation of film by using photosensitive paste P07 and

5 evaluation of properties>

The photo-curing depth of the resulting photosensitive paste P07 was 7.0 μm at an amount of exposure of 400 mJ/cm^2 . A film having a thickness of 7.0 μm was formed on an alumina substrate through screen printing by using this photosensitive paste P07.

10 Thereafter, the resulting film was cured by application of ultraviolet light under a condition of 400 mJ/cm^2 through a photomask, and uncured portions were removed with acetone. As a result, the minimum L/S was 35/30 μm .

The aspect ratio of the pattern was determined from
15 dimensions after firing. The resulting aspect ratio was 0.27.

Subsequently, a film having a thickness of 25 μm was formed on an alumina substrate by using this photosensitive paste P07 through screen printing, and the resulting film was cured by application of ultraviolet light at 400 mJ/cm^2 . This operation
20 was repeated, so that a paste film having a thickness of 100 μm was formed. The Vickers hardness of this coating film measured 10.5 Hv.

Comparative Example No. 8

25 <Preparation of photosensitive paste P08>

The following materials were blended and kneaded, so that

photosensitive paste P08 containing a polymer outside of the scope of the present invention was prepared.

AgPd powder (average particle diameter = 2.0 μm): 75 percent by weight

5 acrylic polymer (polymer): 6.8 percent by weight

trimethylolpropane EO-modified (degree of polymerization n = 1) triacrylate (photosensitive monomer): 4.1 percent by weight
(photosensitive monomer/(photosensitive monomer + polymer) = $4.1/(4.1 + 6.8) = 0.38$)

10 2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:
1.5 percent by weight

2,4-diethylthioxanthone: 0.3 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:
1.1 percent by weight

15 dipropylene glycol monomethyl ether: 11.2 percent by weight

<Formation of film by using photosensitive paste P08 and evaluation of properties>

The photo-curing depth of the resulting photosensitive paste
20 P08 was 6.5 μm at an amount of exposure of 400 mJ/cm^2 . A film having a thickness of 6.5 μm was formed on an alumina substrate through screen printing by using this photosensitive paste P08. Thereafter, the resulting film was cured by application of ultraviolet light under a condition of 400 mJ/cm^2 through a
25 photomask, and uncured portions were removed with a 0.5 percent by weight sodium carbonate aqueous solution. As a result, the

minimum L/S was 25/25 μm .

The aspect ratio of the pattern was determined from dimensions after firing. The resulting aspect ratio was 0.41.

Subsequently, a film having a thickness of 25 μm was formed on an alumina substrate by using this photosensitive paste P08 through screen printing, and the resulting film was cured by application of ultraviolet light at 400 mJ/cm². This operation was repeated, so that a paste film having a thickness of 100 μm was formed. The Vickers hardness of this coating film measured 13.6 Hv.

The conditions, various properties, and the like of Example Nos. 1 to 21 measured as described above are shown in Tables 1 to 5, and the conditions, various properties, and the like of Comparative example Nos. 1 to 8 are shown in Tables 6 and 7.

Table 1

Example No.	Example No. 1	Example No. 2	Example No. 3	Example No. 4
Paste	P1	P2	P3	P4
Inorganic powder 1	Ag	Ag	Ag	Ag
Inorganic powder 2	-	-	-	-
Inorganic powder 1 particle diameter (μm)	2.8	2.8	2.8	2.8
Inorganic powder 2 particle diameter (μm)	-	-	-	-
Inorganic powder content (percent by weight)	75.0	80.0	85.0	71.0
Photo-curing depth (at 400 mJ/cm ²) (μm)	18.9	16.2	12.8	22.1
Vickers hardness (HV)	24.6	15.2	10.6	30.2
Resolution (L/S)	20/20	25/25	25/25	25/20
Aspect ratio after firing	0.80	0.69	0.61	0.68
Formation object (substrate/film)	alumina	alumina	alumina	alumina
Method for forming thick film pattern	screen printing	screen printing	screen printing	screen printing
Monomer 1	A	A	A	A
Monomer 2	-	-	-	B

Degree of polymerization of ethylene oxide structure	0	0	0	1
Double bond concentration of photosensitive monomer ($\text{mmol} \cdot \text{g}^{-1}$)	10.38	10.38	10.38	8.70
Amount of polymer (percent by weight)	0	0	0	0
Monomer/ (monomer + polymer)	1.0	1.0	1.0	1.0
Organic solvent	PMG	-	ECA	-
Amount of solvent (percent by weight)	3.0	0	1.3	0
Development solution	ethanol	ethanol	ethanol	acetone
Various additives	-	-	-	thixotropic agent
Drying step	needless	needless	needless	needless

Table 2

Example No.	Example No. 5	Example No. 6	Example No. 7	Example No. 8
Paste	P5	P6	P7	P8
Inorganic powder 1	Ag	Ag	Ag	Ag and Al ₂ O ₃ -coated Ag
Inorganic powder 2	-	-	glass	glass
Inorganic powder 1 particle diameter (μm)	2.8	2.8	2.8	2.8/2.0
Inorganic powder 2 particle diameter (μm)	-	-	1.5	1.5
Inorganic powder content (percent by weight)	75.0	80.0	80.0/2.4	56.3/18.8/2.4
Photo-curing depth (at 400 mJ/cm ²) (μm)	18.5	17.0	15.2	13.9
Vickers hardness (HV)	26.5	17.1	14.8	15.4
Resolution (L/S)	25/25	30/30	25/30	25/30
Aspect ratio after firing	0.62	0.55	0.51	0.45
Formation object (substrate/film)	alumina	alumina	PET	PET
Method for forming thick film pattern	screen printing	screen printing	screen printing	screen printing
Monomer 1	A	A	A	A
Monomer 2	B	B	-	-
Degree of polymerization of ethylene oxide structure	1	1	0	0
Double bond concentration of photosensitive monomer (mmol·g ⁻¹)	8.70	8.70	10.38	10.38
Amount of polymer (percent by weight)	0	0	0	0
Monomer/ (monomer + polymer)	1.0	1.0	1.0	1.0
Organic solvent	-	PMG	-	DGME
Amount of solvent (percent by weight)	0	0.7	0	1.3
Development solution	acetone	acetone	ethanol	ethanol
Various additives	-	-	-	-
Drying step	needless	needless	needless	needless

Table 3

Example No.	Example No. 9	Example No. 10	Example No. 11	Example No. 12
Paste	P9	P10	P11	P12
Inorganic powder 1	Cu	Cu	AgPd	Ag
Inorganic powder 2	-	-	-	-
Inorganic powder 1 particle diameter (μm)	2.5	2.5	2.0	3.0
Inorganic powder 2 particle diameter (μm)	-	-	-	-
Inorganic powder content (percent by weight)	77.0	80.0	80.0	75.0
Photo-curing depth (at 400 mJ/cm^2) (μm)	15.8	14.8	14.1	17.1
Vickers hardness (HV)	17.8	16.9	15.7	27.5
Resolution (L/S)	30/30	25/25	20/20	30/30
Aspect ratio after firing	0.59	0.53	0.7	0.61
Formation object (substrate/film)	alumina	alumina	alumina	alumina
Method for forming thick film pattern	screen printing	screen printing	screen printing	screen printing
Monomer 1	A	A	A	C
Monomer 2	-	-	-	-
Degree of polymerization of ethylene oxide structure	0	0	0	0
Double bond concentration of photosensitive monomer ($\text{mmol}\cdot\text{g}^{-1}$)	10.38	10.38	10.38	10.14
Amount of polymer (percent by weight)	0	0	0	0
Monomer/ (monomer + polymer)	1.0	1.0	1.0	1.0
Organic solvent	DGME/PMG	-	-	-
Amount of solvent (percent by weight)	6.0	0	0	0
Development solution	ethanol	ethanol	ethanol	ethanol
Various additives	-	DBP	-	thixotropic agent
Drying step	need	needless	needless	needless

Table 4

Example No.	Example No. 13	Example No. 14	Example No. 15	Example No. 16
Paste	P13	P14	P15	P16
Inorganic powder 1	Ag	Ag	Ag	Ag
Inorganic powder 2	-	-	-	-
Inorganic powder 1 particle diameter (μm)	2.8	2.8	2.8	2.8
Inorganic powder 2 particle diameter (μm)	-	-	-	-
Inorganic powder content (percent by weight)	75.0	75.0	75.0	75.0
Photo-curing depth (at 400 mJ/cm^2) (μm)	16.7	16.0	15.6	14.2
Vickers hardness (HV)	19.9	18.5	18.4	18.0
Resolution (L/S)	25/25	25/25	25/25	30/25
Aspect ratio after firing	0.68	0.62	0.60	0.48
Formation object (substrate/film)	alumina	alumina	alumina	alumina
Method for forming thick film pattern	screen printing	screen printing	screen printing	screen printing
Monomer 1	B	A	A	A
Monomer 2	-	-	-	-
Degree of polymerization of ethylene oxide structure	1	0	0	0
Double bond concentration of photosensitive monomer ($\text{mmol}\cdot\text{g}^{-1}$)	10.38	10.38	10.38	10.38
Amount of polymer (percent by weight)	0.5	1.0	1.0	2.0
Monomer/ (monomer + polymer)	0.97	0.95	0.90	0.86
Organic solvent	DGME	DGME	DGME	DGME
Amount of solvent (percent by weight)	5.0	1.0	4.0	3.8
Development solution	ethanol	ethanol	ethanol	ethanol
Various additives	thixotropic agent	-	thixotropic agent	thixotropic agent
Drying step	needless	needless	needless	needless

Table 5

Example No.	Example No. 17	Example No. 18	Example No. 19	Example No. 20	Example No. 21
Paste	P17	P18	P19	P20	P21
Inorganic powder 1	Ag	Ag	Ag	Ag	Ag
Inorganic powder 2	-	-	-	-	-
Inorganic powder 1 particle diameter (μm)	3.0	3.0	3.0	3.0	2.8
Inorganic powder 2 particle diameter (μm)	-	-	-	-	-
Inorganic powder content (percent by weight)	75.0	75.0	75.0	75.0	80.0
Photo-curing depth (at 400 mJ/cm^2) (μm)	12.5	13.8	11.3	11.0	15.5
Vickers hardness (HV)	15.8	14.3	13.2	13.1	15.1
Resolution (L/S)	30/25	35/35	35/30	40/30	25/20
Aspect ratio after firing	0.55	0.35	0.30	0.29	0.65
Formation object (substrate/film)	alumina	alumina	alumina	alumina	alumina
Method for forming thick film pattern	screen printing	screen printing	screen printing	screen printing	screen printing
Monomer 1	B	D	B	B	A
Monomer 2	-	-	-	-	-
Degree of polymerization of ethylene oxide structure	1	0	3	4	0
Double bond concentration of photosensitive monomer ($\text{mmol}\cdot\text{g}^{-1}$)	7.01	12.05	4.34	3.64	10.38
Amount of polymer (percent by weight)	0	0	0	0	0
Monomer/ (monomer + polymer)	1.0	1.0	1.0	1.0	1.0
Organic solvent	-	-	-	-	-
Amount of solvent (percent by weight)	0	0	0	0	0
Development solution	ethanol	ethanol	ethanol	ethanol	ethanol
Various additives	thixo-tropic agent	thixo-tropic agent	thixo-tropic agent	thixo-tropic agent	ultra-violet absorber
Drying step	needless	needless	needless	needless	needless

Table 6

Example No.	Comparative example No. 1	Comparative example No. 2	Comparative example No. 3	Comparative example No. 4
Paste	P01	P02	P03	P04
Inorganic powder 1	Ag	Ag	Ag	Ag
Inorganic powder 2	-	-	-	-
Inorganic powder 1 particle diameter (μm)	2.8	2.8	2.8	2.8
Inorganic powder 2 particle diameter (μm)	-	-	-	-
Inorganic powder content (percent by weight)	75.0	75.0	74.0	77.0
Photo-curing depth (at 400 mJ/cm^2) (μm)	9.6	6.7	9.1	7.2
Vickers hardness (HV)	17.3	15.4	18.8	12.7
Resolution (L/S)	30/30	30/30	25/25	30/25
Aspect ratio after firing	0.32	0.27	0.43	0.31
Formation object (substrate/film)	alumina	alumina	alumina	alumina
Method for forming thick film pattern	screen printing	screen printing	screen printing	screen printing
Monomer 1	A	A	B	B
Monomer 2	-	-	-	-
Degree of polymerization of ethylene oxide structure	0	0	1	1
Double bond concentration of photosensitive monomer ($\text{mmol} \cdot \text{g}^{-1}$)	10.38	10.38	7.01	7.01
Amount of polymer (percent by weight)	3.0	4.0	6.2	5.5
Monomer/ (monomer + polymer)	0.81	0.74	0.49	0.53
Organic solvent	DGME	DGME	DGME	PMG/DGME
Amount of solvent (percent by weight)	2.0	3.5	11.6	1.2/8.5
Development solution	ethanol	sodium carbonate	sodium carbonate	sodium carbonate
Various additives	thixotropic agent	thixotropic agent	thixotropic agent	-
Drying step	needless	needless	need	need

Table 7

Example No.	Comparative example No. 5	Comparative example No. 6	Comparative example No. 7	Comparative example No. 8
Paste	P05	P06	P07	P08
Inorganic powder 1	Ag	Cu	Cu	AgPd
Inorganic powder 2	glass powder	-	glass powder	-
Inorganic powder 1 particle diameter (μm)	2.8	2.5	2.5	2.0
Inorganic powder 2 particle diameter (μm)	1.5	-	1.5	-
Inorganic powder content (percent by weight)	80.0/2.4	80.0	80.0/0.4	75.0
Photo-curing depth (at 400 mJ/cm ²) (μm)	7.0	7.9	7.0	6.5
Vickers hardness (HV)	8.1	12.7	10.5	13.6
Resolution (L/S)	30/30	30/30	35/30	25/25
Aspect ratio after firing	0.33	0.20	0.27	0.41
Formation object (substrate/film)	PET	PET	alumina	alumina
Method for forming thick film pattern	screen printing	screen printing	screen printing	screen printing
Monomer 1	B	B	B	B
Monomer 2	-	-	-	-
Degree of polymerization of ethylene oxide structure	1	1	1	1
Double bond concentration of photosensitive monomer (mmol·g ⁻¹)	7.01	7.01	7.01	7.01
Amount of polymer (percent by weight)	4.1	5.6	7.8	6.8
Monomer/ (monomer + polymer)	0.41	0.40	0.26	0.38
Organic solvent	ECA	DGME	DGME	DGME
Amount of solvent (percent by weight)	7.5	6.9	7.2	11.2
Development solution	sodium carbonate	sodium carbonate	acetone	sodium carbonate
Various additives	-	DBP	-	-
Drying step	need	need	need	need

In Tables 1 to 7, monomer A, monomer B, monomer C, monomer D, PMG, ECA, DGME, DBP, and polymer denote the following respective substances.

monomer A: dipentaerythritol hexaacrylate

monomer B: trimethylolpropane EO-modified triacrylate

monomer C: trimethylolpropane triacrylate

monomer D: triallyl isocyanurate

5 PMG: pentamethylene glycol

ECA: ethylcarbitol acetate

DGME: dipropylene glycol monomethyl ether

DBP: dibutyl phthalate

polymer: methacrylic acid-methyl methacrylate copolymer

10 molecular weight $M_w = 15,000$

As is clear from the above-described Example Nos. 1 to 21 and Comparative Example Nos. 1 to 8, the photosensitive paste containing no polymer and the photosensitive paste containing a polymer within the scope of the present invention exhibit photo-
15 curing depths of about 10 μm or more, and thick film patterns having large thicknesses and exhibiting high dimension precision and high shape precision can be formed efficiently by using the photosensitive pastes within the scope of the present invention, although the photosensitive pastes of Comparative Example Nos. 1
20 to 8 containing a polymer outside of the scope of the present invention exhibit photo-curing depths of less than 10 μm , so that a pattern having an adequate thickness cannot be formed by using such a photosensitive paste.

In each of the above-described Examples and Comparative
25 examples, the exposure treatment is conducted through the photomask. However, it is also possible to apply laser light or

UV light with a wavelength of about 300 nm to about 420 nm to a photosensitive paste film by using Maskless Exposure System (produced by Ball semiconductor Inc., for example), so as to cure the photosensitive paste film. In that case, a desired pattern
5 can be formed by moving a stage indicating the photosensitive paste film in accordance with the pattern information input beforehand.

Fig. 3 is a sectional view showing an electronic component (ceramic multilayer substrate) according to another preferred
10 embodiment of the present invention. This ceramic multilayer substrate is preferably a ceramic multilayer substrate provided with electrodes (inner layer copper pattern, surface layer copper pattern, and the like) composed of thick film patterns formed by using the photosensitive paste (photosensitive copper paste) of
15 various preferred embodiments of the present invention.

A ceramic multilayer substrate 11 in the present preferred embodiment is preferably formed by laminating insulator layers 12a, 12b, 12c, 12d, 12e, and 12f and dielectric layers 13a and 13b. In the inside thereof, capacitor patterns, coil patterns,
20 strip lines, and the like are formed from inner layer copper patterns 15 and via holes 16.

Furthermore, a chip component 20, e.g., a chip capacitor, a thick film resistor 21, a semiconductor IC 22, and the like are disposed on one main surface of the ceramic multilayer substrate
25 11, and are connected to their respective surface layer copper patterns 17 or inner layer copper patterns 15.

In this ceramic multilayer substrate 11, the inner layer copper patterns (thick film patterns) 15 and surface layer copper patterns (thick film patterns) 17 have widths of about 50 μm and film thicknesses of about 5 μm or more.

5 A method for manufacturing this ceramic multilayer substrate 11 will be described below.

 A glass powder, a ceramic powder, and an organic vehicle are mixed, so that an insulator ceramic green sheet slurry is prepared. Likewise, a dielectric ceramic green sheet slurry is
10 prepared. Each of the resulting slurries is molded into the shape of a sheet by a doctor blade method or the like, and is dried at a temperature of about 50°C to about 150°C, so that insulator ceramic green sheets and dielectric ceramic green sheets are produced. The ceramic green sheets are provided with
15 their respective via holes as needed.

 A photosensitive paste (photosensitive copper paste) according to a preferred embodiment of the present invention, the paste having a predetermined photo-curing depth, is prepared. The photosensitive copper paste is applied to a support to form a
20 photosensitive copper paste film. The film thickness of the photosensitive copper paste film is set in consideration of the photo-curing depth.

 This photosensitive copper paste film is subjected to an exposure treatment and, thereafter, is developed, so that a thick
25 film pattern having a predetermined shape is formed on the support.

The thick film pattern formed on the support is transferred to the ceramic green sheet (insulator ceramic green sheet or dielectric ceramic green sheet (an object to which the transfer is conducted)) produced as described above, so that a capacitor pattern, a coil pattern, or the like is formed.

The ceramic green sheets provided with thick film patterns are stacked, press-bonded and, thereafter, fired at a predetermined temperature. Subsequently, chip components, semiconductor ICs, and the like are mounted, thick film resistors are printed and, thereby, the ceramic multilayer substrate 11 as shown in Fig. 3 is formed.

In the production of this ceramic multilayer substrate 11, since the thick film patterns (inner layer copper patterns, surface layer copper patterns, and the like) are formed by the method for forming a thick film pattern according to various preferred embodiments of the present invention, it becomes possible to form a highly precise, fine thick film pattern having a large film thickness on a ceramic green sheet by a transfer method. Consequently, a ceramic multilayer substrate satisfactorily suitable for an increase in signal speed and an increase in wiring density can be produced efficiently by stacking and press-bonding ceramic green sheets provided with the above-described thick film patterns and, thereafter, firing them at a predetermined temperature.

In the above-described present preferred embodiment, the ceramic multilayer substrate is preferably shown as the

electronic component. However, the present invention can be applied to circuit substrates, which are not multilayered, and other various electronic components.

Fig. 4 and Fig. 5 are drawings showing another example of electronic components according to a further preferred embodiment of the present invention.

Fig. 4 is a perspective view showing an appearance of a chip coil 31 as an example of the above-described electronic components. Fig. 5 is a perspective exploded view showing a component body 32 of the chip coil 31 shown in Fig. 4.

The chip coil 31 is provided with an insulating substrate 33, and insulator films 34, 35, 36, and 37 disposed by using a photolithography photosensitive paste (insulator photosensitive paste) according to a preferred embodiment of the present invention are laminated sequentially on this insulating substrate 33. Furthermore, conductor films 38, 39, 40, and 41 disposed by using a photolithography photosensitive paste (conductor photosensitive paste) according to a preferred embodiment of the present invention are located on the insulating substrate 33 and the insulator films 34, 35, and 36, respectively.

The component main body 32 preferably includes the insulating substrate 33, insulator films 34 to 37, and conductor films 38 to 41. External terminals 42 and 43 are disposed on opposed two end surfaces of the component body 32.

The conductor films 38 to 41 are connected to each other through via hole connection portions 44 to 46 arranged to

penetrate the insulator films 34 to 36, respectively, so as to form a predetermined coil pattern as a whole. In Fig. 5, the location of each of the via hole connection portions 44 to 46 is simply indicated by an alternate long and short dashed lines, and individual penetration conductors constituting via hole connection portions 44 to 46 are not shown in the drawing.

In more detail, the conductor film 38 is electrically connected to the conductor film 39 through the via hole connection portion 44 disposed in the insulator film 34.

Likewise, the conductor film 39 is electrically connected to the conductor film 40 through the via hole connection portion 45 disposed in the insulator film 35. The conductor film 40 is electrically connected to the conductor film 41 through the via hole connection portion 46 disposed in the insulator film 36.

The two end portions of the conductor films 38 to 41 connected to each other to form the coil pattern, as described above, that is, one end portion of the conductor film 38 and one end portion of the conductor film 41, are electrically connected to the external terminals 42 and 43, respectively.

A method for manufacturing this chip coil 31 will be described below.

As shown in Fig. 5, a photolithography photosensitive paste (conductor photosensitive paste) according to a preferred embodiment of the present invention is applied to the insulating substrate 33 formed from, for example, alumina. For the application of this photolithography photosensitive paste

(conductor photosensitive paste), various methods, e.g., a screen printing method, a spin coating method, and a doctor blade method, can be used.

5 The photosensitive paste film (conductor paste film) applied and formed as described above is dried and, thereafter, is subjected to an exposure treatment through a photomask having a predetermined pattern.

10 A development treatment is conducted to remove unnecessary portions of the photosensitive paste film (conductor paste film). Thereafter, for example, a spiral conductor film 38 is formed by conducting a firing treatment in air under a predetermined condition.

15 The photolithography photosensitive paste (insulator photosensitive paste) according to a preferred embodiment of the present invention is applied to the insulating substrate 33 while covering the conductor film 38. A method similar to that in the above-described case of application of the conductor photosensitive paste can be used for this coating.

20 The photosensitive paste film (insulator paste film) formed as described above is dried. Subsequently, the resulting photosensitive paste film (insulator paste film) is subjected to an exposure treatment through a photomask having a predetermined pattern in order to form a hole having a diameter of, for example, about 50 μm (not shown in the drawing) and being used for a via
25 hole connection portion 44.

A development treatment is conducted to remove unnecessary

portions. Thereafter, for example, an insulator film 34 having a hole for the via hole connection portion 44 is formed by conducting a firing treatment in air under a predetermined condition.

5 A conductor paste is filled in the above-described hole for the via hole connection portion 44, and drying is conducted, so that the via hole connection portion 44 is formed in the insulator film 34.

10 A spiral conductor film 39 is formed on the insulator film 34 by a method similar to that in the above-described case of formation of the conductor film 38.

15 Alternatively, the hole of the via hole connection portion may be filled in with the conductor paste and the photosensitive paste film (conductor paste film) may be formed by applying the conductor paste once, followed by exposure and development. Thereafter, the via hole conductor and the conductor film may be fired simultaneously.

20 Subsequently, the insulator film 35, the conductor film 40, the insulator film 36, and the conductor film 41 are formed sequentially by a method similar to that described above. After the insulator film 37 used for protection is formed, the external terminals 42 and 43 are formed, so that the chip coil 31 exhibiting an appearance as shown in Fig. 4 is completed.

25 According to the above-described manufacturing method, the photolithography photosensitive paste (insulator photosensitive paste) of a preferred embodiment of the present invention is used

for forming the insulator films 34 to 37. Therefore, in particular, fine holes for the via hole connection portions 44 to 46 to be disposed in the insulator films 34 to 36 can simply and easily be formed with excellent precision with respect to the shape and the location.

Likewise, since the conductor films 38 to 41 are formed by using the photosensitive paste (conductor photosensitive paste) of a preferred embodiment of the present invention, fine and high-density patterns can simply and easily be provided to these conductor films 38 to 41 with high precision. In particular, thick conductor films 38 to 41 can easily be formed as compared with those in the case where a usual screen printing method or the like is applied. Consequently, the chip coil 31 is allowed to have excellent high-frequency properties.

It is also possible to use the photosensitive paste according to various preferred embodiments of the present invention for only one of the conductor photosensitive paste and the insulator photosensitive paste.

The present invention is not limited to the above-described embodiments, and various applications and modifications can be made within the scope of the invention.

According to various preferred embodiments of the present invention, it is possible to efficiently form via photolithography a thick film pattern having a large thickness and exhibiting high dimension precision and high shape precision and, by extension, it becomes possible to produce high-

performance, highly reliable ceramic multilayer substrates, chip coil components, and the like, efficiently.

Therefore, the present invention can be widely applied to various electronic components and methods for manufacturing them.